

CLAIM AMENDMENTS

1 - 14. (canceled)

15. (currently amended) A MOCVD apparatus for gas phase deposition [[with]] comprising:

a chamber;

a partition subdividing the chamber into at least two compartments;

respective gas inlets {4, 5}, characterized by opening into the compartments and connectable to respective gas supplies; and

means for flexibly switching the inlets and thus flexibly introducing gases into the apparatus.

16. (currently amended) The MOCVD apparatus according to claim 15 ~~characterized in that~~ , further comprising between the gas inlets {4, 5} and the ~~supply vessels~~ supplies for the gases to be fed into the apparatus, gas collecting lines ~~{51, 52, 53} are provided~~ in which there are arranged at least two three-way valves {V1, V2, V3} shiftable between a first position feeding one of the gases to one of the compartments and the other of the gases to the other of the compartments and a second position feeding the other gas to the one compartment and the one gas to the other compartment.

17. (canceled)

1 18. (new) The MOCVD apparatus according to claim 15,
2 further comprising
3 quick-connect couplings between the inlets and the
4 supplies.